

Correction to Band Gap Engineering with Ultralarge Biaxial Strains in Suspended Monolayer MoS₂

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We found an error in the labeling of the AFM cross sections in Figure 1c, which were labeled with the wrong strain values. The updated version of Figure 1 contains the correct values. There are no other errors in the paper.

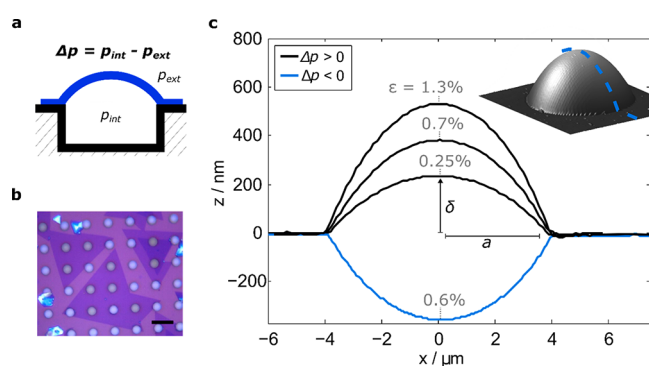


Figure 1.